1986—Volume 133
Author and Subject Index
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The Computer-Derived 1986 Journal Index

The Publication Committee of the Society recommended the use of a computer-derived index in 1968, and this practice is planned to be continued. These indices refer only to *Journal* articles, reviews, brief communications, discussions, and news and reviews listed in the contents pages. They do not include meeting papers, abstracts, and news items. These indices were prepared for the *Journal* by Amron Information Services, Union, New Jersey.

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3. For a detailed explanation and meaning of symbols and abbreviations, see the sample pages before the individual author and title index and subject index.
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ROBERT P. FRANKENTHAL
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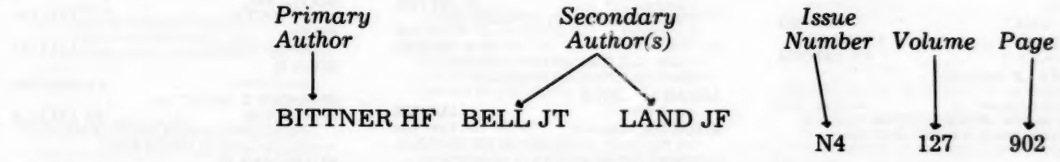

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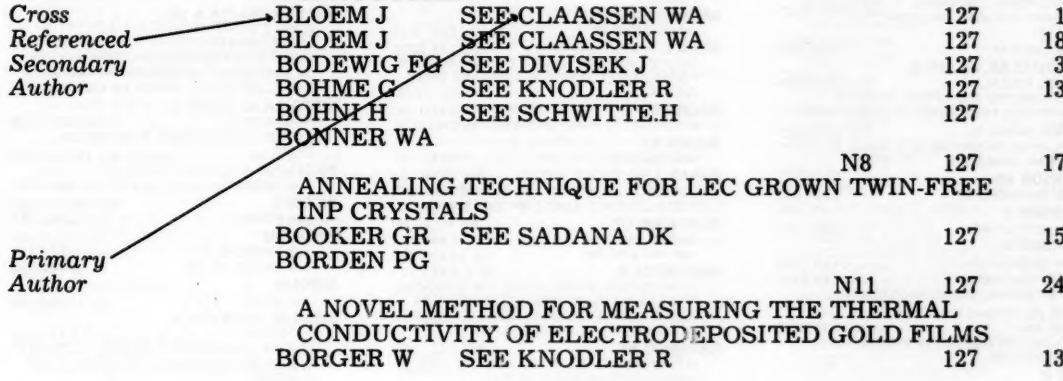

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